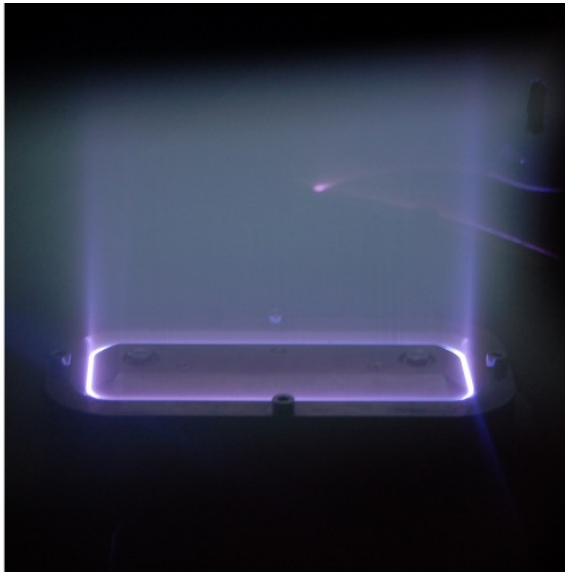


Ion Beam Source IBS - 280



Ion Beam Source IBS - 280

The extended ion source IBS-280 is designed to generate a linear flow of working gas ions with an energy of 500-2500 eV.

IBS-280 is used for ionic cleaning, ionic etching, ionic polishing, ionic surface modification, assisting during spraying.

IBS-280 is designed for a wide range of applications: ion cleaning, etching, polishing, surface modification

Parameter	Value
Supply voltage	500 – 5000 V
<i>The average ion energy is equal to half of the supply voltage</i>	
Maximum beam current	250 mA
<i>For argon at a flow rate of not more than 1.6 l / h</i>	
Beam shape	rectangular, hollow
Beam size (L x W x T)	254 x 42 x 5mm
Length x Width x Thickness	
Maximum voltage	5500 V
Maximum operating current	500 mA
Maximum gas consumption	1,5-2,0 l / h
Maximum coolant consumption	1 l / min
Maximum working pressure in chambers	10 Pa
Chamber working pressure range	0,001-1 Pa
Weight no more than	5.2 kg

Ion Beam Source IBS - 280 basic dimensions, versions

